

# Terra-Pixel APS for CALICE

Progress meeting 10<sup>th</sup> Nov 2005

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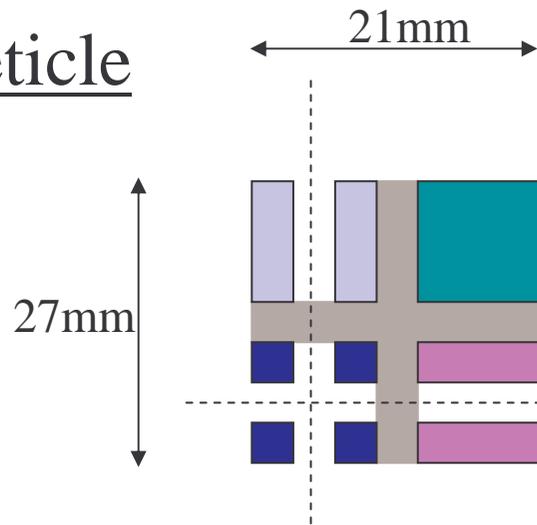
# FAB processes

X-FAB SEMICONDUCTOR FOUNDRIES

- XC035
  - Standard 0.35um process from XFAB
  - 5um epitaxial layer
  - Qualified for stitching
  - This process will now be “frozen”
- XH035
  - High voltage variant of the 0.35um process
  - 15um epitaxial layer
  - NOT qualified for stitching (yet – tbc)
  - Triple well technology
  - Assura parasitic extraction models

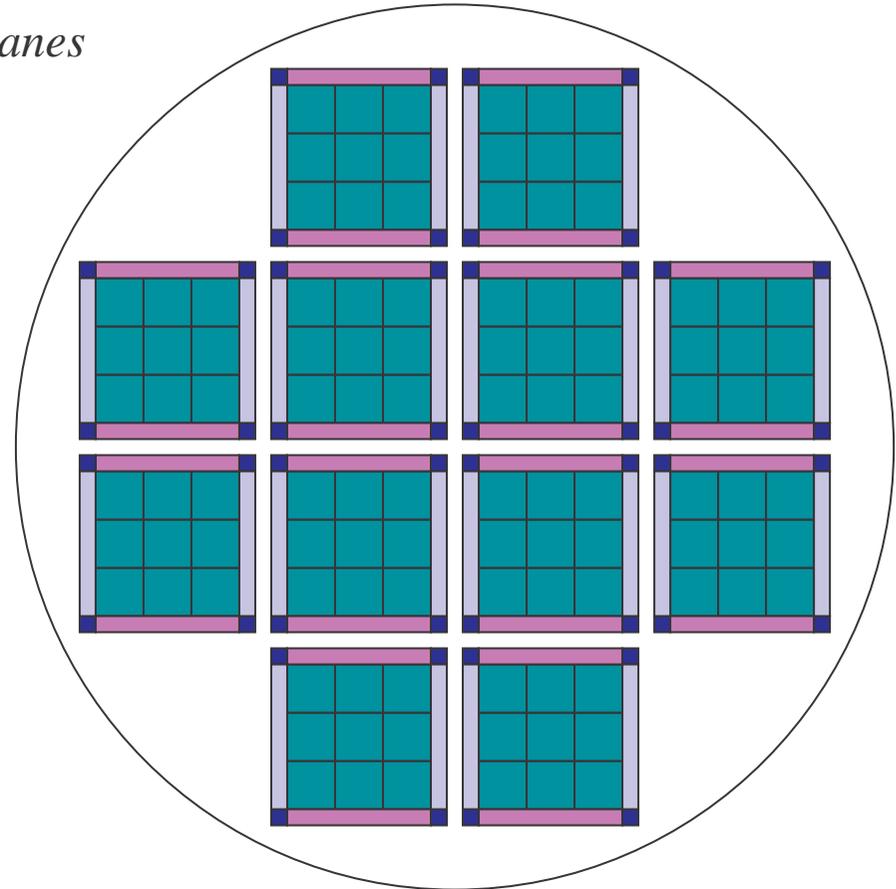
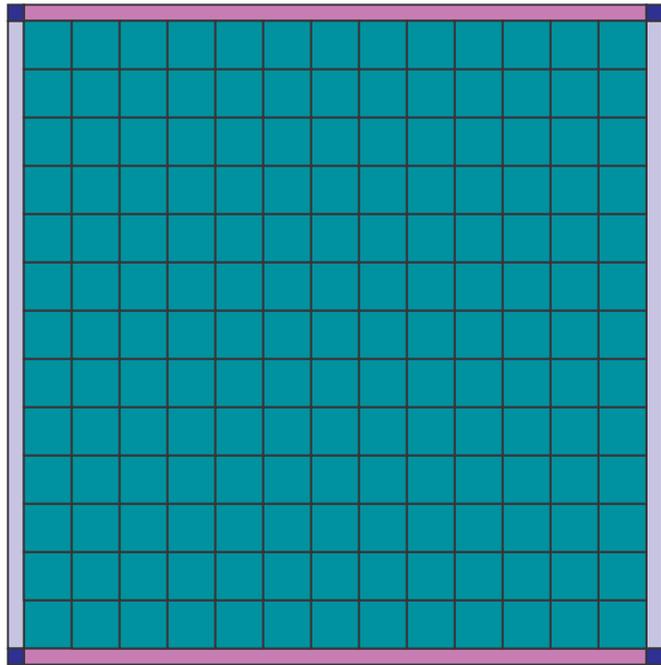
# How stitching works

Reticle



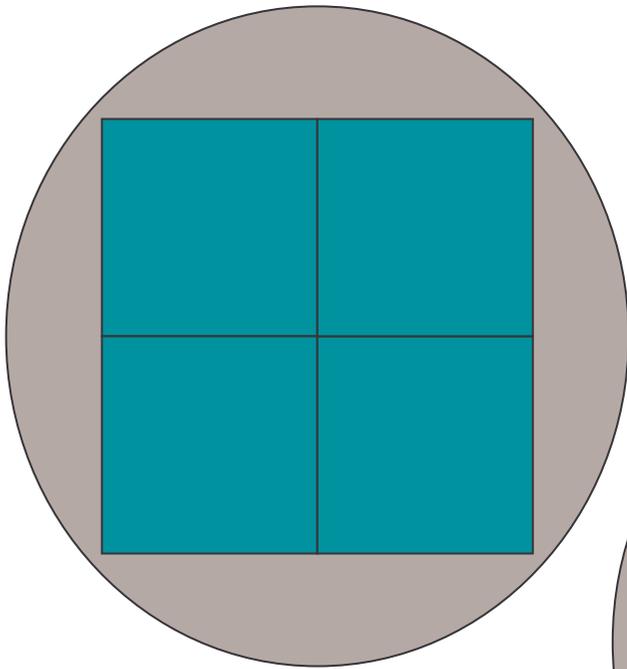
*Blading space*

*Scribe lanes*

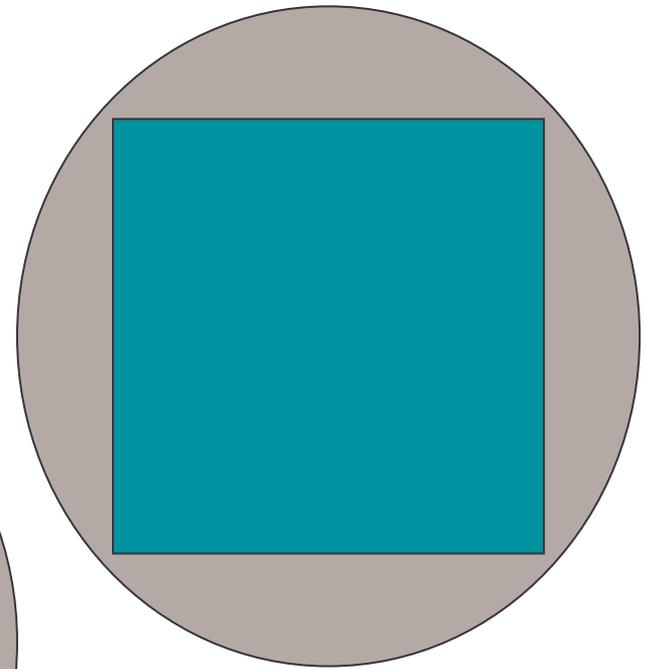


# Stitching

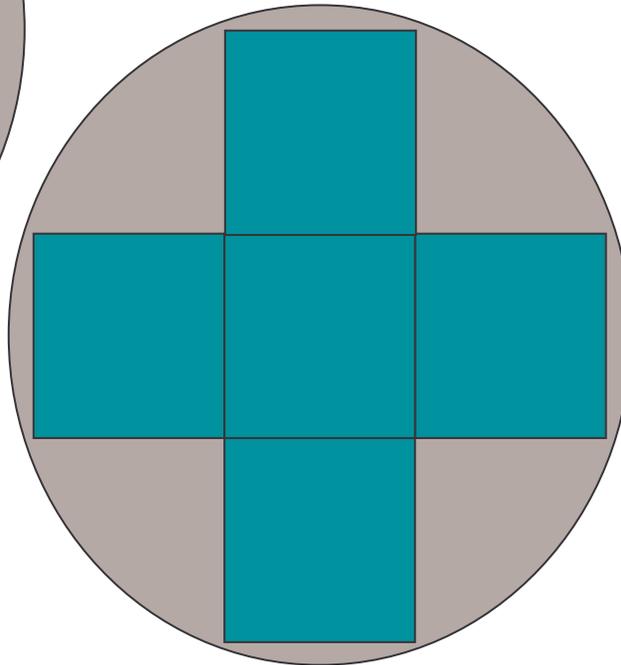
4 x 6.2cm chips



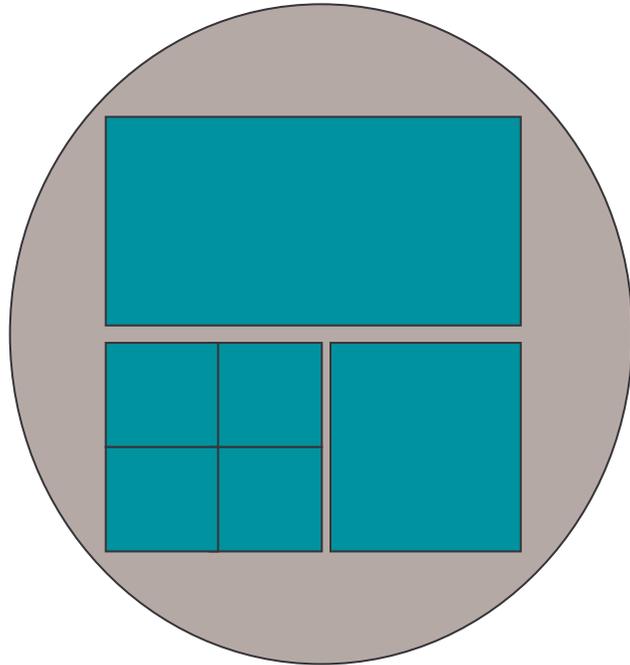
1 x 13cm chip



5 x 5.6cm chips

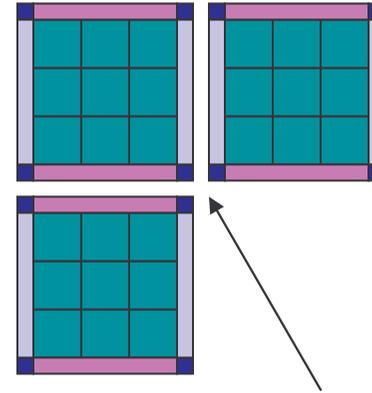


## Test structures?

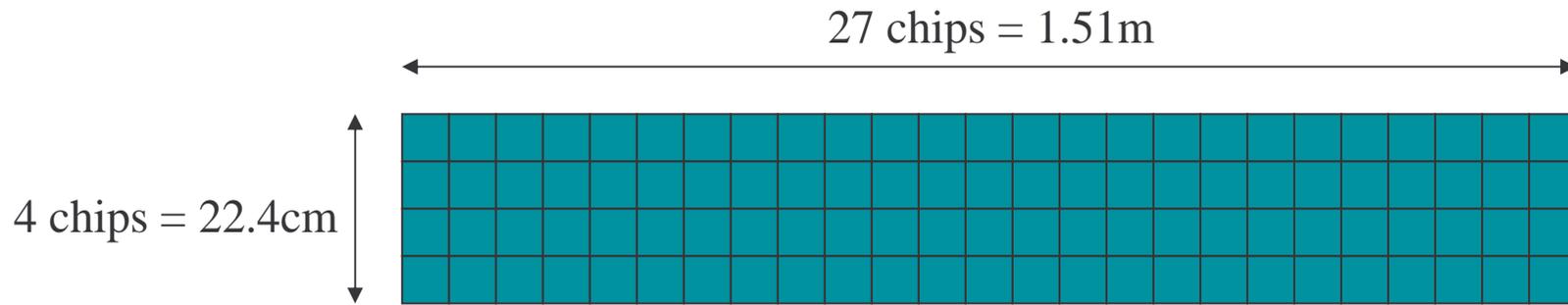


- Full 13cm readout length
- Smaller arrays for tests

## Need to fully dice?

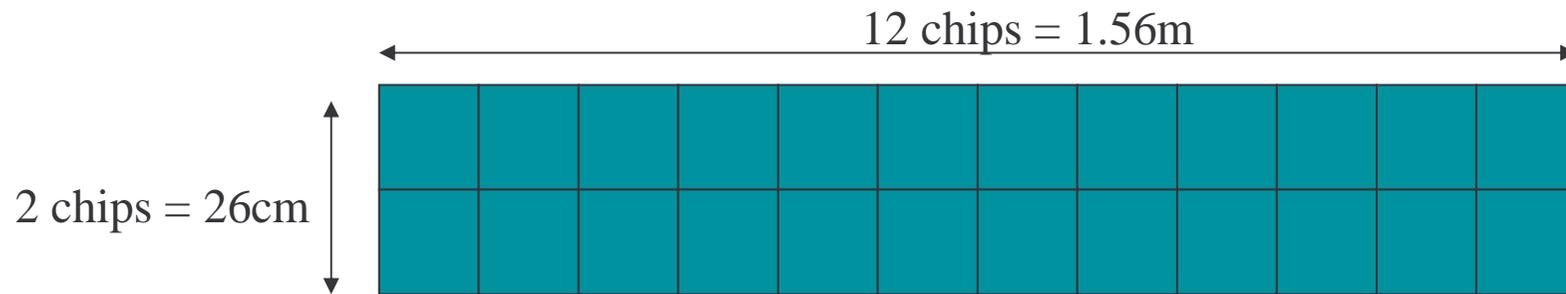


- 150um scribe lanes, could remain uncut...
- Could cut a 13x13cm area from the wafer containing an array of chips with 150um spacings?
- Yield?
- Bonding / alignment complications?
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108 Chips @ 5.6cm = 22 wafers

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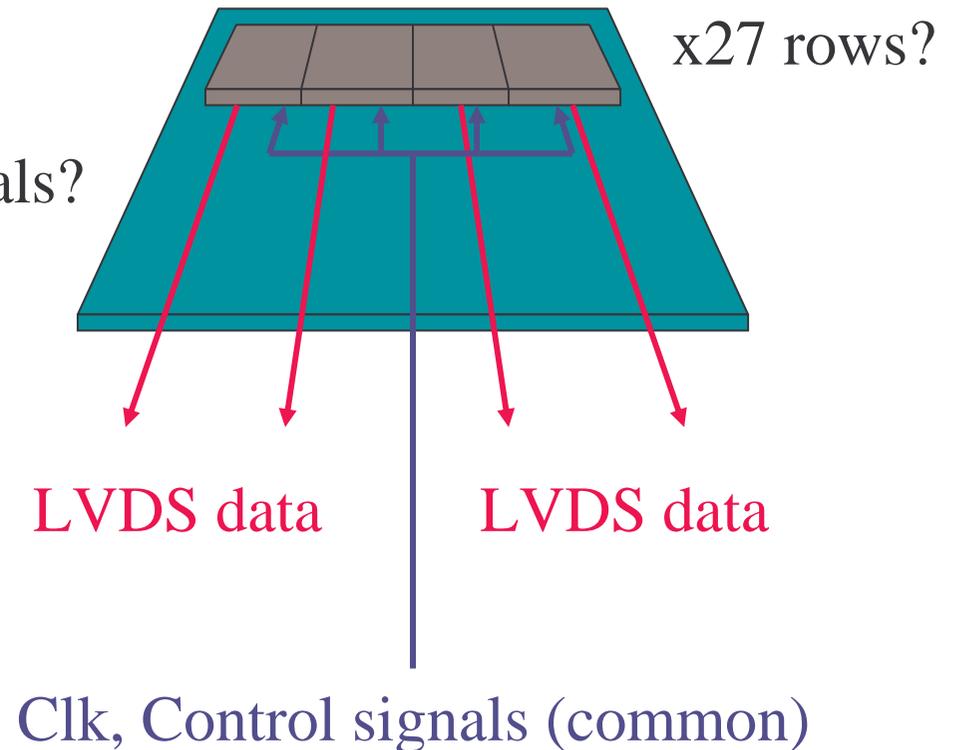


24 Chips @ 13cm = 24 wafers

# PCB concerns

~100 LVDS pairs to FPGA  
Power planes, local decoupling  
Differential clock and control signals?  
Well designed clock distribution!  
Synchronisation? PLLs?

Serial chain of all chips on-  
board for setup programming?  
Optical links along PCB?  
Less control signals the better!



# PCB bump bonding

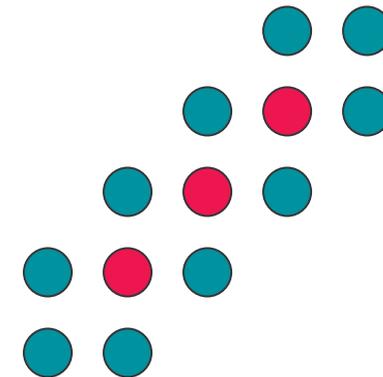
- XFAB:

*\*\*\* It's feasible as far as the XFAB silicon goes. The pad structures (shapes) will have to be defined by your flip-chip assembly contractor . XFAB will want the metal/via arrangement and basic layer construction to be retained according to the DRC. Many of our customers use our wafers in bumping (solder & gold) applications.*

**No circuits under bond pad!**

- IBM kit has some rules

- In-house IBM service, C4 structure: Lead/Tin ball
- 50um pad, ~250um pitch: “4 mil balls on 9 mil pitch”
- Active and Dummy terminals for mechanical support
- Complex rules for pad layout:
  - Asymmetry on all 4 sides
  - Asymmetry within 2mm of chip centre
  - Mixture of dummy and actual pads
  - Outer row < 250um from chip edge
  - Circular patterns disallowed



C4 is old technology – plenty of techniques

Need to consult PCB/bonding house!

Many of these rules impossible for repeating stitched design!

# Data Access times

- Per physics event
  - 2000 hits per layer
  - If these were all on a single chip...
  - @6.6Mhz, reading 2 values per pixel, takes 600uS to read those 2k pixels
  - How many “physics events” per train?

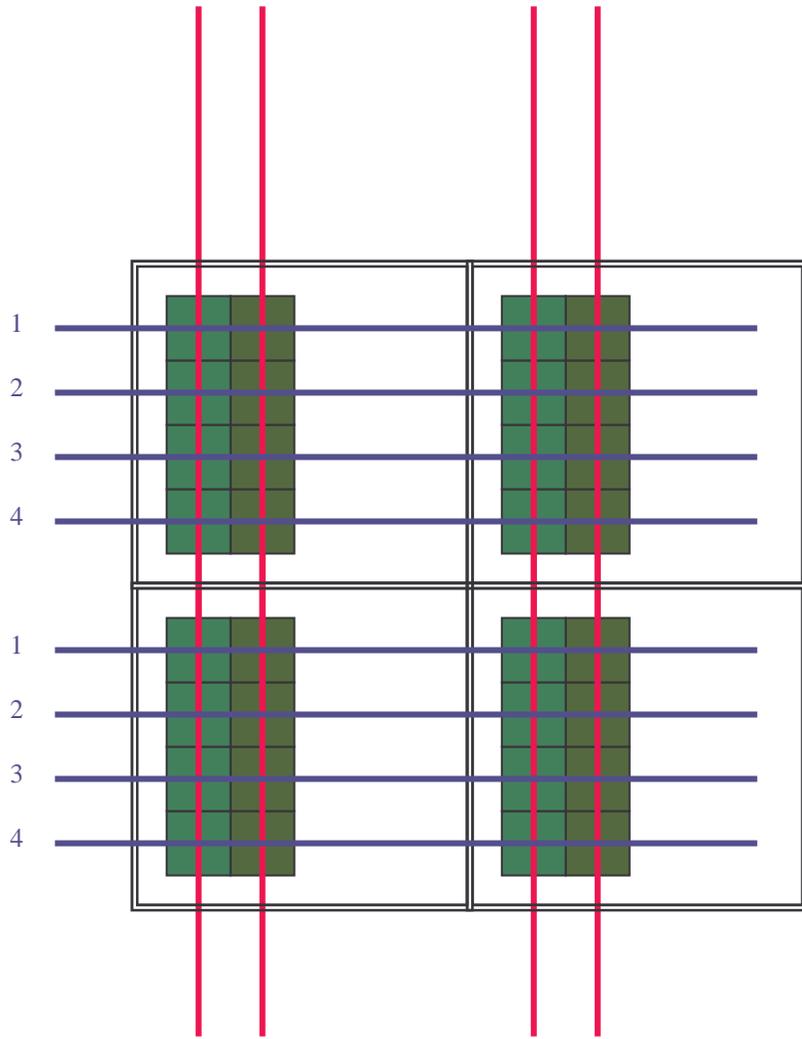
# Power Consumption

- Example: Single clock line driven to every pixel...
  - Calculation for a 1mm square, 50um pixels
  - 0.22pF estimated line capacitance (per col)
  - Clock rate 6.6Mhz (150ns repetition) at 3.3V
  - 319uW per square mm
  - Allowing 2% duty cycle, à **6.4uW per sq mm**

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*(for one global signal to 400 pixels)*

# Perpendicular memory cells?

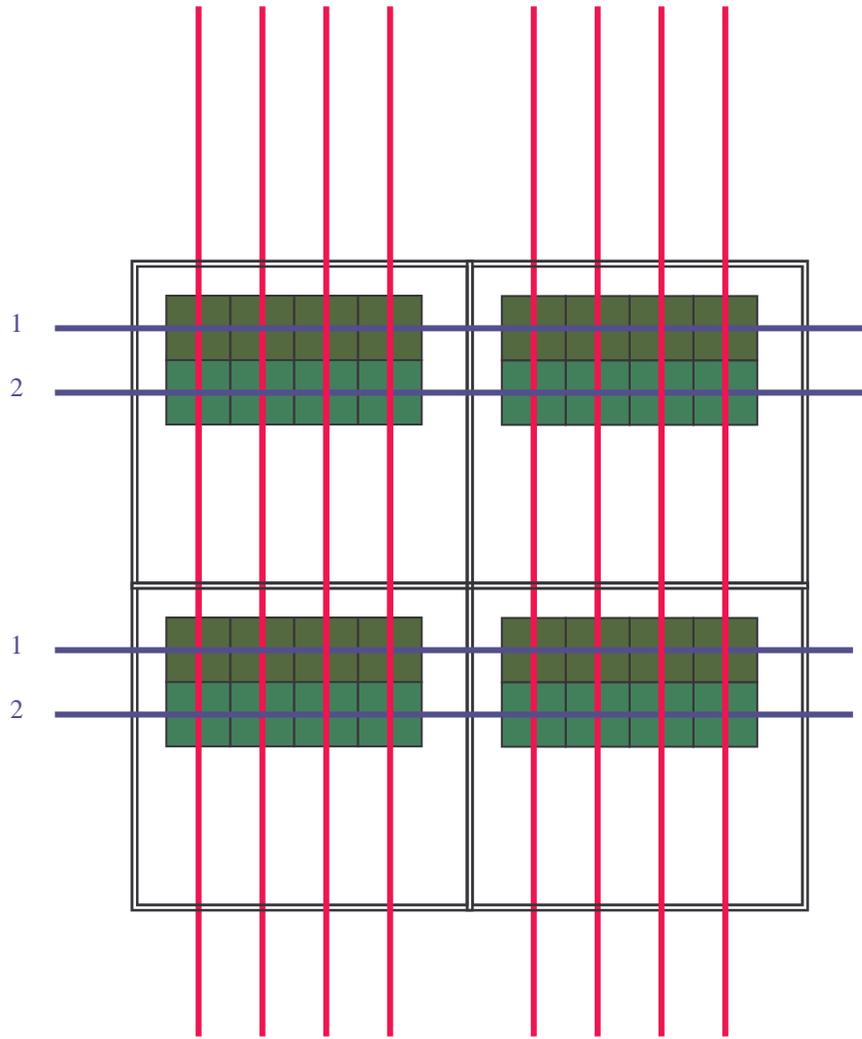


Parallel write  
Serial read

- + less sense amps
- + serial out consistent with link to FPGA
- + Din/out perpendicular

- Need 16 1-bit shift register cells in every cell instead of 1
- Different column lengths depending on hits
-

# Perpendicular memory cells 2?



Parallel read  
Serial write

Timing code is shifted along  
through pixels

Or generated from single bit  
shift registers in neighbour  
pixels

Reduced power load to  
distribute timing code

Added complexity/scrambled  
data

Would require some set-up  
time before pulse train

# “*Current Focus*”

- Register selection for write and read access
- Suitable low-power clocked comparator with adjustable threshold/offset
- Analog circuits in the pixel
  - Continuous reset mode
  - How to “add” multiple pixel values
- DRAM Cells
  - Stacked capacitors are possible
  - Simulate and compare lifetime with “physics events” statistics to establish suitability of dynamic storage
  - Sample layouts to indicate cell size